

Notice of References Cited	Application/Control No. 10/796,376	Applicant(s)/Patent Under Reexamination HOULIHAN ET AL.	
	Examiner Amanda C. Walke	Art Unit 1752	Page 1 of 1

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*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
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	B	US-2005/0036183	02-2005	Yeo et al.	359/015
	C	US-6,875,555	04-2005	Feiring et al.	430/270.1
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NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
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	V	Hung et al., "Resist Materials for 157nm Microlithography: An Update", Advances in Resist Technology and Processing XVII (Proceedings of SPIE)" Vol. 4345 pp. 385-391 (2001).
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*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.